

**Application Data Sheet****Application Information**

Application Type::	Regular
Subject Matter::	Utility
CD-ROM or CD-R:	None
Title::	METHOD OF PRODUCING PHASE SHIFT MASK BLANK, METHOD OF PRODUCING PHASE SHIFT MASK, PHASE SHIFT MASK BLANK, AND PHASE SHIFT MASK
Attorney Docket Number::	119162
Total Drawing Sheets::	15
Small Entity::	No

**Applicant Information**

Applicant Authority type::	Inventor
Primary Citizenship Country::	Japan
Status::	Full Capacity
Given Name::	Hiroki
Family Name::	YOSHIKAWA
City of Residence::	Niigata
Country of Residence::	Japan

---

Applicant Authority type::	Inventor
Primary Citizenship Country::	Japan
Status::	Full Capacity
Given Name::	Yukio
Family Name::	INAZUKI
City of Residence::	Niigata
Country of Residence::	Japan

---

Applicant Authority type::	Inventor
Primary Citizenship Country::	Japan

Status:: Full Capacity  
Given Name:: Noriyasu  
Family Name:: FUKUSHIMA  
City of Residence:: Niigata  
Country of Residence:: Japan

---

Applicant Authority type:: Inventor  
Primary Citizenship Country:: Japan  
Status:: Full Capacity  
Given Name:: Hideo  
Family Name:: KANEKO  
City of Residence:: Niigata  
Country of Residence:: Japan

---

Applicant Authority type:: Inventor  
Primary Citizenship Country:: Japan  
Status:: Full Capacity  
Given Name:: Satoshi  
Family Name:: OKAZAKI  
City of Residence:: Niigata  
Country of Residence:: Japan

### Correspondence Information

Correspondence Customer Number:: 25944

Foreign Priority Information			
Country::	Application Number::	Filing Date::	Priority Claimed::
Japan	2003-093280	03/31/2003	Yes
Country::	Application Number::	Filing Date::	Priority Claimed::
Japan	2003-093296	03/31/2003	Yes
Country::	Application Number::	Filing Date::	Priority Claimed::
Japan	2003-093301	03/31/2003	Yes
Assignee Information			
Assignee Name::			
Shin-Etsu Chemical Co., Ltd.			
Street of mailing address::			
6-1, Ohtemachi 2-chome, Chiyoda-ku			
City of mailing address::			
Tokyo			
Country of mailing address::			
Japan			